Centre for Nano Science and Engineering (CeNSE)

Indian Institute of Science

Mask Fabrication Submission Form

Name:

Department or Organization:

Degree Registered (If applicable):

Advisor or supervisor name:

Mask plate size required (3, 4 or 5 Inch):

Pattern area:

Note: For 3” mask plate, 2 inch circle will be writing area, similarly for 4”mask plate it will be 3” and 5” mask plate, writing area will be 4”.

Minimum feature size:

Type of mask Positive (Dark field) and Negative (Bright field) –Mask will be written as per the design submitted (we will not inverse the design)

Note: A positive mask is one, in which the pattern described in your design will eventually pass UV light(chrome will be removed from the mask) and a negative mask is one in which the pattern described in your design will eventually block light (chrome will stay on the pattern area).

File format submitted:

Any specific instruction:

Note: 1.The design files for the mask should be sent to the laser writer In-charge before two days of lithography slot (CIF or GDS-2)
2. User must book one wet bench slot for piranha cleaning of the mask, preferably one day before user performs the first lithography.

Signature of the user Signature of advisor/Supervisor